

ABSTRACT

The present disclosure provides a water supply control method for a semiconductor process device, a diffusion process method, and a semiconductor process device. The water supply control method includes: obtaining water supply time period information that each of the plurality of furnace tubes needs to reserve; according to the water supply time period information that each of the plurality of furnace tubes needs to reserve, updating a reservation queue at a current moment; and according to the water supply time period information in the updated reservation queue, setting the liquid evaporator to be in an available state or an unavailable state for each of the plurality of furnace tubes, such that the liquid evaporator supplies water to only one furnace tube at a time. The present disclosure allows each reserved furnace tube to be supplied with water in a chronological order, thus avoiding manual intervention in the process. By setting the available state or unavailable state of the liquid evaporator for each furnace tube, the liquid evaporator can only be occupied by one furnace tube at a time, thereby reducing the probability of waiting in the process and improving production efficiency.